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Pursuant to 37 CFR 1.8, I, Alfred H. Muratori, hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Assistant Commissioner for Patents, Washington D.C. 20231 on 29 August 2002. (signature) *Alfred H. Muratori*

IN THE UNITED STATES PATENT AND TRADEMARKE OFFICE

Applicant: Hunt/et al.

Group art: 1773

Application No.: 09/748,714

Examiner: Ramsey Zacharia

Filing date: 12 December 2000

For: CHEMICAL VAPOR DEPOSITION METHODS FOR MAKING POWDERS  
AND COATINGS, AND COATINGS MADE USING THESE METHODS

Amendment and Response to Restriction Requirement of 21 August 2002

Assistant Commissioner of Patents

Washington D.C. 20231

Sir:

In response to the restriction requirement dated 21 August 2002 for which a shortened statutory period for response is set to expire 21 September 2002, please amend the above-identified application as follows:

Please delete claims 34-86 without prejudice or disclaimer and add the following new claims 90-98 as follows:

--90) A system for forming a material, comprising:

at least one energy source;

means for directing a precursor material along a first path and into a localized environment of the at least one energy source, to allow the at least one energy source to activate the precursor within gasses;

means for providing at least one source of pressure differential and applying the at least one source of pressure differential to the localized environment of the at least one energy source, such that the localized environment is selectively changed to redirect the gasses from the first path to a redirected path, to thereby cause the gasses to contact a surface and form at least part of the material.

91) The system according to Claim 90, wherein said means for directing the precursor material along the first path comprises a nozzle.

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